

WHAT IS CLAIMED IS:

1 1. A tension mask assembly for a flat cathode ray tube, comprising:

2 a tension mask comprising a plurality of strips separated from one another by a
3 predetermined gap, real bridges connecting adjacent strips to define slots accommodating electron
4 beams to pass, and first and second dummy bridges extending from adjacent strips toward each slot
5 therebetween, said tension mask being installed to include a top surface of said tension mask facing
6 a panel forming a screen and being separated from said panel by a predetermined gap;

7 a plurality of supporting members disposed at opposite sides of said tension mask to support
8 said tension mask; and

9 a plurality of rigid members secured to opposite ends of said supporting members to apply
10 tension to said tension mask, a first etching boundary being formed at an end of said first dummy
11 bridge near to the center of the tension mask being lower with respect to the screen than a second
12 etching boundary formed at an end of said second dummy bridge near to the periphery of said
13 tension mask.

1 2. The tension mask assembly of claim 1, with the vertical center axis of an etched area
2 at the upper end surfaces of said first and second dummy bridges being offset from the vertical center
3 axis of an etched area at the lower end surfaces of said first and second dummy bridges toward the
4 center of said tension mask to accommodate a deflected electron beam being blocked.

1 3. The tension mask assembly of claim 2, with the amount of offset increasing from the

center of said tension mask toward the periphery of said tension mask.

4. The tension mask assembly of claim 1, with an etched area at the upper end surfaces of said first and second dummy bridges being wider than an etched area at the lower end surfaces of said first and second dummy bridges.

5. The tension mask assembly of claim 1, with an etched area at an upper surface above the first etching boundary of said first dummy bridge being wider than an etched area at a lower surface therebelow, and an etched area at a lower surface below the second etching boundary of said second dummy bridge being wider than an etched area at an upper surface thereabove.

6. A tension mask assembly, comprising:
a tension mask including a plurality of strips separated from one another by a predetermined gap, real bridges connecting adjacent strips to define slots accommodating electron beams to pass, and first and second dummy bridges extending from adjacent strips toward each slot therebetween, said tension mask being installed to include a top surface of said tension mask facing a panel forming a screen and being separated from said panel by a predetermined gap, a first etching boundary being formed at an end of said first dummy bridge near to the center of the tension mask being lower with respect to the screen than a second etching boundary formed at an end of said second dummy bridge near to the periphery of said tension mask.

7. The tension mask assembly of claim 6, with the vertical center axis of an etched area

2 at the upper end surfaces of said first and second dummy bridges being offset from the vertical center
3 axis of an etched area at the lower end surfaces of said first and second dummy bridges toward the
4 center of said tension mask to accommodate a deflected electron beam being blocked.

1 8. The tension mask assembly of claim 7, with the amount of offset increasing from the
2 center of said tension mask toward the periphery of said tension mask.

1 9. The tension mask assembly of claim 6, with an etched area at the upper end surfaces
2 of said first and second dummy bridges being wider than an etched area at the lower end surfaces
3 of said first and second dummy bridges.

1 10. The tension mask assembly of claim 6, with an etched area at an upper surface above
2 the first etching boundary of said first dummy bridge being wider than an etched area at a lower
3 surface therebelow, and an etched area at a lower surface below the second etching boundary of said
4 second dummy bridge being wider than an etched area at an upper surface thereabove.